

### Sputtering Au on Si using Sputter#4

**Sputtering Condition:** 5mT, 200W, Ar=45sccm, z=1, tilting=10, and time=120 s

**Result:** the sputtering rate≈17.7nm/min, roughness Ra= 0.430 nm.

Figure 1 Film Thickness=35.3nm.

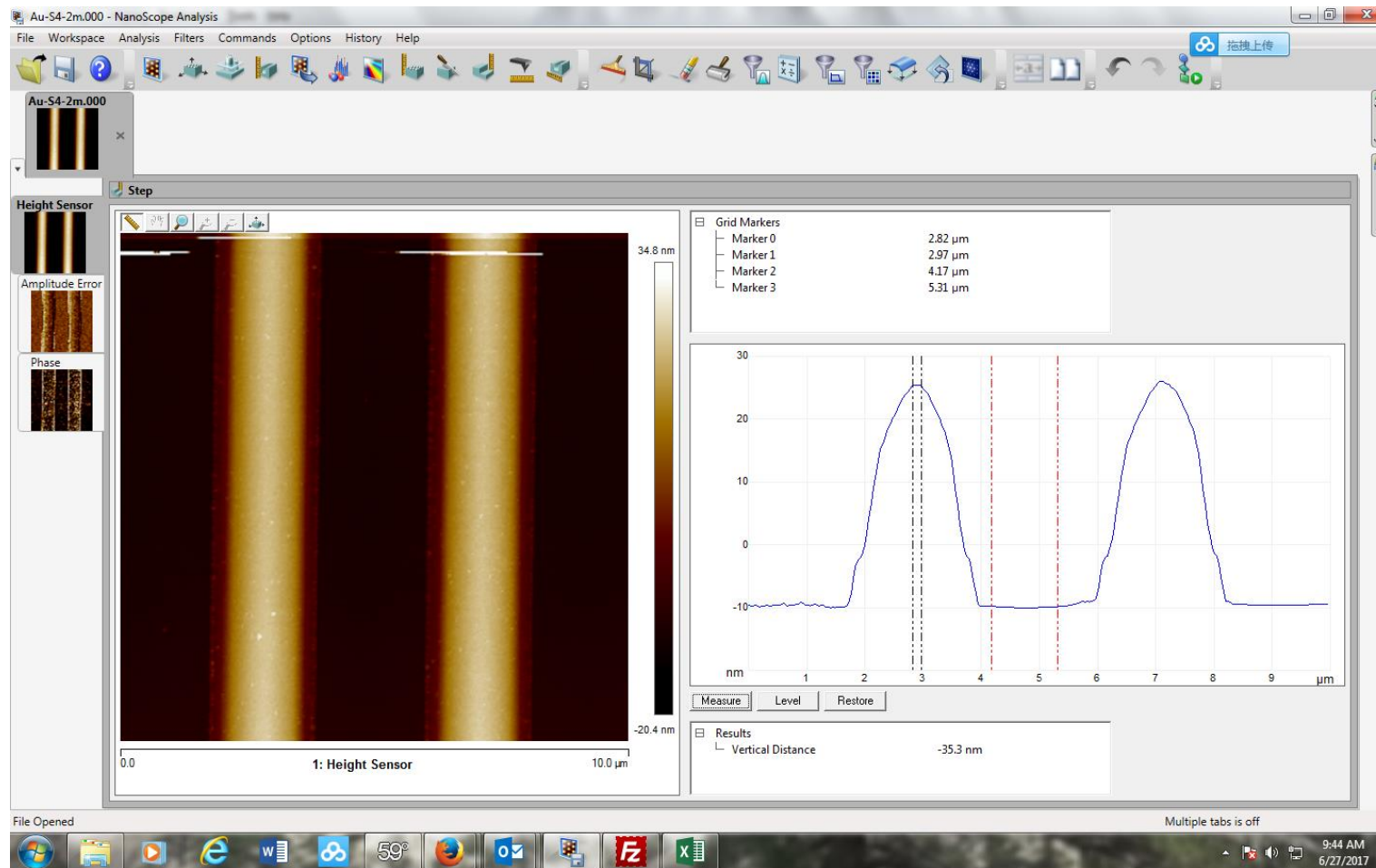


Figure 2 Surface scan by AFM ( $R_a=0.430$  nm)

